

Acknowledgment to Reviewers of *Clean Technologies* in 2021

Clean Technologies Editorial Office

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Rigorous peer-reviews are the basis of high-quality academic publishing. Thanks to the great efforts of our reviewers, *Clean Technologies* was able to maintain its standards for the high quality of its published papers. Thanks to the contribution of our reviewers, in 2021, the median time to first decision was 22 days and the median time to publication was 71 days. The editors would like to extend their gratitude and recognition to the following reviewers for their precious time and dedication, regardless of whether the papers they reviewed were finally published:

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